

Aerosol-Assisted Chemical Vapor Deposition of MSe and MSSe Thin Films from Zinc(II) and Cadmium(II) Single Source Precursors Containing Hybrid Se,X-PNC Ligands

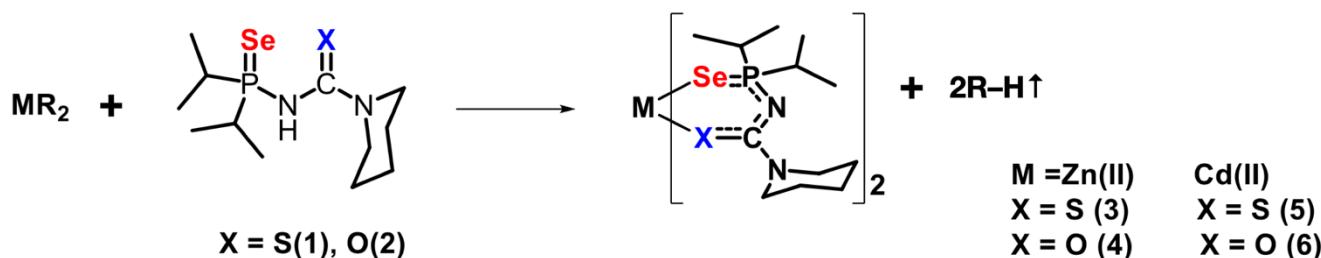
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Notes and references

1. Proligands and Precursors¹⁻³



$iPr_2P(Se)NHC(S)NC_5H_{10}$ (1). Piperidine (3.95 mL, 40 mmol) and $iPr_2P(Se)NC(S)$ (10.17 g, 40 mmol). White solid. Yield: 12.22 g (90%). M.p. 99–101 °C. $^{31}P\{^1H\}$ NMR (C_6D_6 , 298 K, 121.65 MHz, ppm): $\delta = 99.7$ (s) ($^{1}J_{P-Se} = 733.5$ Hz). $^{77}Se\{^1H\}$ NMR (C_6D_6 , 298 K, 57.28 MHz, ppm): $\delta = -441.6$ ($^{1}J_{Se-P} = 733.5$ Hz). 1H NMR (C_6D_6 , 298 K, 300 MHz, ppm): $\delta = 1.01$ (br, 6H, CH_2 -piperidine), 1.24 (2dd, CH_3-iPr^a $^{3}J_{H-H} = 6$ Hz, CH_3-iPr^a $^{3}J_{H-P} = 18$ Hz, CH_3-iPr^b $^{3}J_{H-H} = 6$ Hz, CH_3-iPr^b $^{3}J_{H-P} = 21$ Hz, 12H), 3.26 (br, 4H, NCH_2 -piperidine), 3.68 (dsep, $^{2}J_{H-H} = 6.0$ Hz, $^{2}J_{H-P} = 12$ Hz, 2H, $CH-iPr$), 5.08 (s, NH). $^{13}C\{^1H\}$ NMR (C_6D_6 , 298 K, 75.56 MHz, ppm): $\delta =$

17.8 (d, $^2J_{C-P}$ = 14.1 Hz, CH₃-ⁱPr), 23.5 (CH₂-piperidine), 25.3 (CH₂-piperidine), 29.3 (d, $^1J_{C-P}$ = 50.2 Hz, CH-ⁱPr), 46.3 (NCH₂-piperidine), 178.7 (CS). FTIR (KBr, cm⁻¹): ν = 3226 v(NH), 2959, 2927, 2854 v(CH), 1487, 1443, 1297, 1123, 657 v(CN/NH/CS), 944 v(PN), 539 v(PSe). EI (m/z): 341 corresponding to ⁱPr₂P(Se)NHC(S)NC₅H₁₀. Microanalysis calculated for C₁₂H₂₅N₂SeSP: N = 8.26, C = 42.47, H = 7.43 %. Observed: N = 8.29, C = 42.57, H = 7.48 %.

ⁱPr₂P(Se)NHC(O)NC₅H₁₀ (2). Piperidine (3.95 mL, 40 mmol) and ⁱPr₂P(Se)NC(O) (9.52 g, 40 mmol). White solid. Yield: 10.51 g (85%). M.p. 77-79 °C. ³¹P{¹H} NMR (C₆D₆, 298 K, 121.65 MHz, ppm): δ = 106.8 (s) ($^1J_{P-Se}$ = 751.8 Hz). ⁷⁷Se{¹H} NMR (C₆D₆, 298 K, 57.28 MHz, ppm): δ = -469.4 ($^1J_{Se-P}$ = 751.8 Hz). ¹H NMR (C₆D₆, 298 K, 300 MHz, ppm): δ = 1.00 (br, 6H, CH₂-piperidine), 1.19 (2dd, CH₃-ⁱPr^a $^3J_{H-H}$ = 6 Hz, CH₃-ⁱPr^a $^3J_{H-P}$ = 15 Hz, CH₃-ⁱPr^b $^3J_{H-H}$ = 6 Hz, CH₃-ⁱPr^b $^3J_{H-P}$ = 21 Hz, 12H), 2.81 (br, 4H, NCH₂-piperidine), 3.01 (dsep, $^2J_{H-H}$ = 6.0 Hz, $^2J_{H-P}$ = 9 Hz, 2H, CH-ⁱPr), 5.11 (s, NH). ¹³C{¹H} NMR (C₆D₆, 298 K, 75.56 MHz, ppm): δ = 17.6 (d, $^2J_{C-P}$ = 16.05 Hz, CH₃-ⁱPr), 24.2 (CH₂-piperidine), 24.1 (CH₂-piperidine), 25.8 (CH₂-piperidine), 29.1 (d, $^1J_{C-P}$ = 50.2 Hz, CH-ⁱPr), 45.7 (NCH₂-piperidine), 153.73 (CO). FTIR (KBr, cm⁻¹): ν = 3239 v(NH), 2964, 2936, 2855 v(CH), 1436, 1227, 1024, 663 v(CN/NH), 1624 v(CO), 930 v(PN), 531 v(PSe). DART+ (m/z): 323 corresponding to ⁱPr₂P(Se)NHC(O)NC₅H₁₀. Microanalysis calculated for C₁₂H₂₅N₂SeOP: N = 8.67, C = 44.58, H = 7.79 %. Observed: N = 8.59, C = 44.49, H = 7.84 %.

[Zn{ⁱPr₂P(Se)NC(S)NC₅H₁₀-κ²-Se,S}₂] (3). 2.9 mmol of **1** and 1.45 mmol of ZnEt₂. White solid. Yield: 0.98 g (89%). M.p. 122-124 °C. ³¹P{¹H} NMR (C₆D₆, 298 K, 121.65 MHz, ppm): δ = 61.8 (s) ($^1J_{P-Se}$ = 524.31 Hz). ⁷⁷Se{¹H} NMR (C₆D₆, 298 K, 57.28 MHz, ppm): δ = -330.0 ($^1J_{Se-P}$ = 524.31 Hz). ¹H NMR (C₆D₆, 298 K, 300 MHz, ppm): δ = 1.12-1.20 (m, 24H, CH₃-ⁱPr), 1.23 (br, 4H, CH₂-piperidine), 1.33 (br, 8H, CH₂-piperidine), 2.21-2.40 (m, 4H, CH-ⁱPr), 3.55 (br, 4H, NCH₂-piperidine), 3.93 (br, 4H, NCH₂-piperidine). ¹³C{¹H} (C₆D₆, 298 K, 75.56 MHz, ppm): δ = 16.1 (CH₃-ⁱPr), 23.7 (CH₂-piperidine), 24.8 (CH₂-piperidine) 30.7 (CH-ⁱPr), 45.6 (NCH₂-piperidine), 48.9 (NCH₂-piperidine), 174.3 (CS). FTIR (KBr, cm⁻¹): ν = 2961, 2928, 2864 v(CH), 1493, 1433, 1408, 1217 v(CN/CS), 968 v(PN), 509 v(PSe). EI (m/z): 741 corresponding to [Zn(ⁱPr₂P(Se)NC(S)NC₅H₁₀-κ²-Se,S)₂]⁺. Microanalysis calculated for C₂₄H₄₈N₄Se₂S₂P₂Zn: N = 7.55, C = 38.85, H = 6.52%. Observed: N = 7.62, C = 38.69, H = 6.65%.

[Zn{ⁱPr₂P(Se)NC(O)NC₅H₁₀-κ²-Se,O}₂] (4). 3.1 mmol of **2** and 1.55 mmol of ZnEt₂. White solid. Yield: 0.90 g (87%). M.p. 113-115 °C. ³¹P{¹H} NMR (C₆D₆, 298 K, 121.65 MHz, ppm): δ = 54.58 (s) ($^1J_{P-Se}$ = 488 Hz). ⁷⁷Se{¹H} NMR (C₆D₆, 298 K, 57.28 MHz, ppm): δ = -370.55 ($^1J_{Se-P}$ = 488 Hz). ¹H NMR (C₆D₆, 298 K, 300 MHz, ppm): (2d, δ = 1.33, $^3J_{H-H}$ = 7, CH₃-ⁱPr^b; δ = 1.39, $^3J_{H-H}$ = 7, CH₃-ⁱPr^a, 24H), 2.16 (oc, , $^3J_{H-H}$ = 7 Hz, $^2J_{H-P}$ = 7 Hz, 4H, CH-ⁱPr), 1.52 (br, 12H, CH₂-piperidine), 3.71 (br, 8H, NCH₂-piperidine). ¹³C{¹H} (C₆D₆, 298 K, 75.56 MHz, ppm): δ = 17.5 (d, $^2J_{C-P}$ = 2 Hz, CH₃-ⁱPr^b), 17.23 (CH₃-ⁱPr^a), 25.39 (CH₂-piperidine), 25.45 (CH₂-piperidine), 31.65 (d, $^1J_{C-P}$ = 54 Hz, CH-ⁱPr), 49.52 (NCH₂-piperidine), 51.89 (NCH₂-piperidine), 163 (CS). FTIR (KBr, cm⁻¹): ν = 2961, 2926, 2849 v(CH), 1429, 1289, 1020, 649 v(CN), 1476 v(CO), 914 v(PN), 526 v(PSe). DART+ (m/z): **711** corresponding to [Zn(ⁱPr₂P(Se)NC(O)NC₅H₁₀-κ²-Se,O)₂]⁺. Microanalysis calculated for C₂₄H₄₈N₄Se₂O₂P₂Zn: N = 7.89, C = 40.60, H = 6.82 %. Observed: N = 7.96, C = 40.65, H = 7.0 %.

[Cd{ⁱPr₂P(Se)NC(S)NC₅H₁₀-κ²-Se,S}₂] (5). 2.9 mmol of **1** and 1.45 mmol of CdMe₂. White solid. Yield: 1.08 g (95%). M.p. 119-121 °C. ³¹P{¹H} NMR (C₆D₆, 298 K, 121.65 MHz, ppm): δ = 60.79 (s) ($^1J_{P-Se}$ = 524.0 Hz). ⁷⁷Se{¹H} NMR (C₆D₆, 298 K, 57.28 MHz, ppm): δ = -337.7 ($^1J_{Se-P}$ = 523.0 Hz). ¹H NMR (C₆D₆, 298 K, 300 MHz, ppm): (2t, δ = 1.14, $^3J_{H-H}$ = 7, $^3J_{H-P}$ = 7 CH₃-ⁱPr^b; δ = 1.20, $^3J_{H-H}$ = 7, $^3J_{H-P}$ = 7 CH₃-ⁱPr^a, 24H), 1.22 (br, 4H, CH₂-piperidine), 1.35 (br, 8H, CH₂-piperidine), 2.40 (dsep, $^3J_{H-H}$ = 7.0 Hz, $^2J_{H-P}$ = 11 Hz, CH-ⁱPr, 4H), 3.55 (br, 4H, NCH₂-piperidine), 3.98 (br, 4H, NCH₂-piperidine). ¹³C{¹H} NMR (C₆D₆, 298 K, 75.56 MHz, ppm): (2d, δ = 16.16, $^2J_{C-P}$ = 4 Hz, CH₃-ⁱPr^b; δ = 16.42, $^2J_{C-P}$ = 2 Hz, CH₃-ⁱPr^a), 23.80 (CH₂-piperidine), 25.0

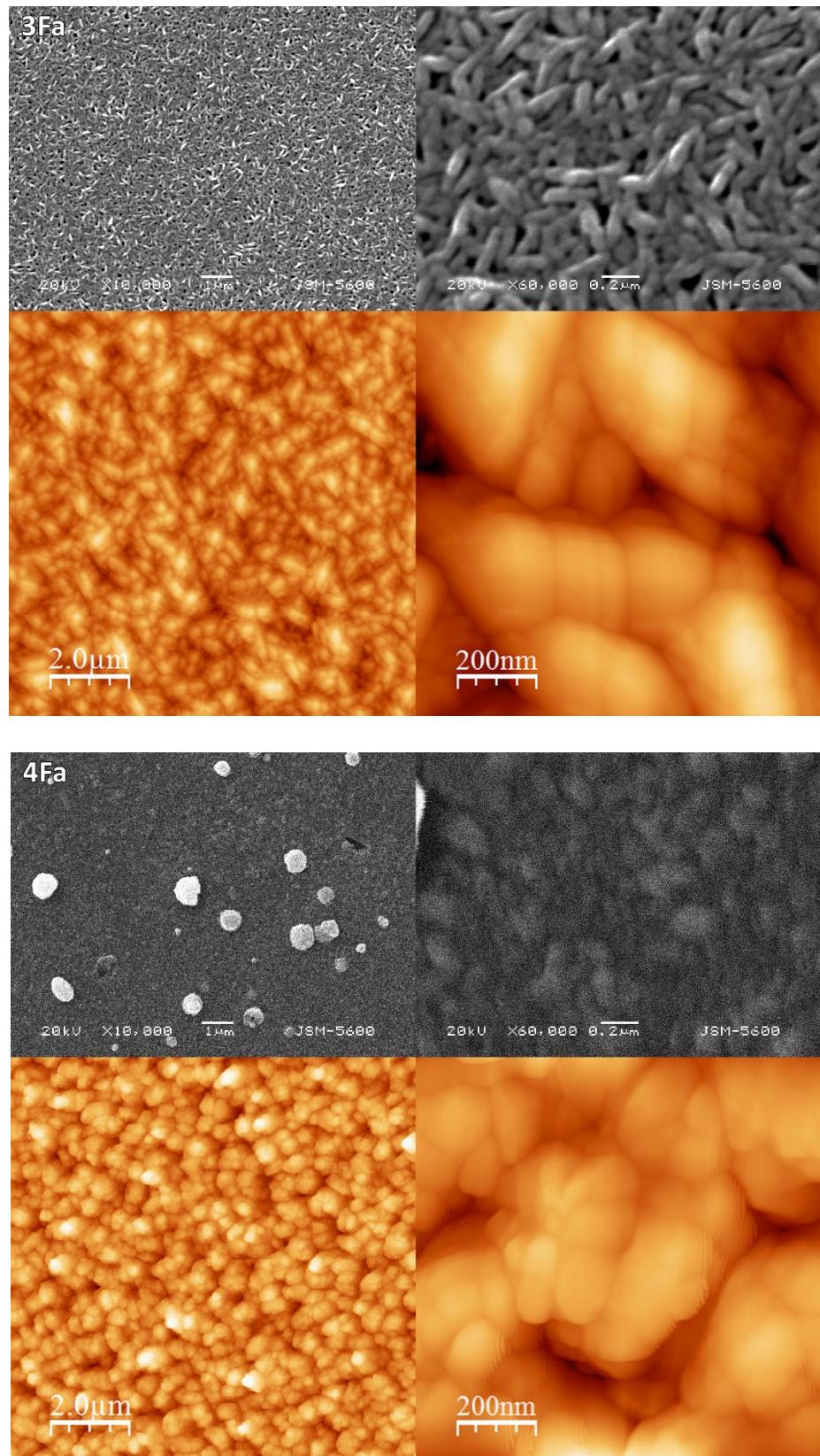
(CH₂-piperidine), 31.14 (d, ¹J_{C-P} = 63 Hz, CH-ⁱPr), 45.80 (NCH₂-piperidine), 48.88 (NCH₂-piperidine), 174.19 (CSe). FTIR (KBr, cm⁻¹): v = 2962, 2929, 2864 v(CH), 1487, 1433, 1404, 1215 v(CN/CS), 966 v(PN), 511 v(PSe). DART+ (m/z): 789 corresponding to [Cd{ⁱPr₂P(Se)NC(S)NC₅H₁₀-κ²-Se,S}₂⁺]. Microanalysis calculated for C₂₄H₄₈N₄Se₂S₂P₂Cd: N = 7.1, C = 36.53, H = 6.13 %. Observed: N= 7.19, C = 36.39, H = 6.23 %.

[Cd{ⁱPr₂P(Se)NC(O)NC₅H₁₀-κ²-Se,O}₂] (6). 3.1 mmol of **2** and 1.55 mmol of CdMe₂. White solid. Yield: 1.09 g (93%). M.p. 120–122 °C. ³¹P{¹H} NMR (C₆D₆, 298 K, 121.65 MHz, ppm): δ = 52.63 (s) (¹J_{P-Se} = 476.70 Hz). ⁷⁷Se{¹H} NMR (C₆D₆, 298 K, 57.28 MHz, ppm): δ = -366.4 (¹J_{Se-P} = 475 Hz). ¹H NMR (C₆D₆, 298 K, 300 MHz, ppm): (4d, δ = 1.11, ³J_{H-H} = 7, CH₃-ⁱPr^d; δ = 1.16, ³J_{H-H} = 7, CH₃-ⁱPr^c; δ = 1.27, ³J_{H-H} = 7, CH₃-ⁱPr^b; δ = 1.33, ³J_{H-H} = 7, CH₃-ⁱPr^a), 1.43 (m, 12H, CH₂-piperidine), 2.16 (dsep, ³J_{H-H} = 7.0 Hz, ²J_{H-P} = 9 Hz, CH-ⁱPr, 4H), 3.20 (m, 8H, NCH₂-piperidine). ¹³C{¹H} NMR (C₆D₆, 298 K, 75.56 MHz, ppm): δ = 16.70 (d, ²J_{C-P} = 3 Hz, CH₃-ⁱPr^b), 17.08 (CH₃-ⁱPr^a), 25.15 (CH₂-piperidine), 26.24 (CH₂-piperidine), 32.12 (d, ¹J_{C-P} = 66 Hz, CH-ⁱPr), 45.18 (NCH₂-piperidine), 164.5 (CO). FTIR (KBr, cm⁻¹): v = 2959, 2926, 2848 v(CH), 1429, 1280, 1026, 626 v(CN), 1487 v(CO), 916 v(PN), 526 v(PSe). DART+ (m/z): 759 corresponding to [Cd{ⁱPr₂P(Se)NC(O)NC₅H₁₀}₂⁺]. FAB+ (m/z): 1193 corresponding to [Cd₂{ⁱPr₂P(Se)NC(O)NC₅H₁₀}₃⁺]. Microanalysis calculated for C₄₈H₉₆Cd₂N₈O₄P₄Se₄: N = 7.40, C = 38.08, H = 6.39%. Observed: N= 7.33, C = 37.97, H = 6.45%.

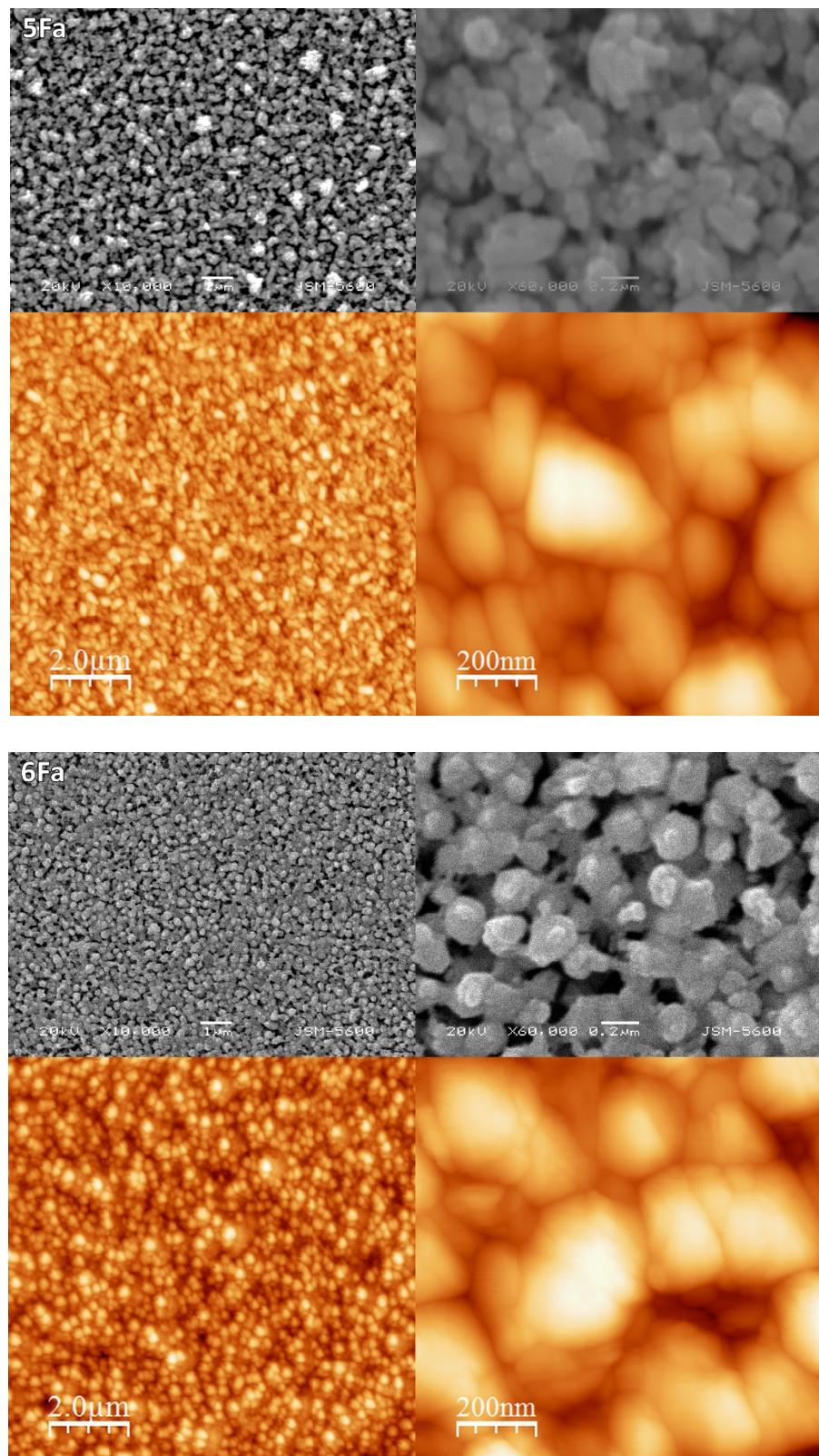
2. **Table S1.** Crystallographic Data for compounds **4**, **5** and **6**.

Compound	4	5	6
Formula	C ₂₄ H ₄₈ N ₄ O ₂ P ₂ Se ₂ Zn	C ₂₄ H ₄₈ CdN ₄ P ₂ S ₂ Se ₂	C ₄₈ H ₉₆ Cd ₂ N ₈ O ₄ P ₄ Se ₄
M [g/mol]	709.89	789.04	1513.84
Temperature	298(2) K	298(2) K	298(2) K
Crystal size (mm)	0.402 x 0.309 x 0.156	0.437 x 0.372 x 0.114	0.287 x 0.211 x 0.140
Crystal system	Triclinic	Monoclinic	Monoclinic
Space group	P -1 (2)	C 2/c (15)	P2 ₁ /c (14)
ρ_{calc} (g cm⁻³)	1.460	1.519	1.521
Z	2	4	2
a (Å)	9.0915(3)	16.1883(2)	11.8582(11)
b (Å)	11.0372(3)	17.1917(2)	13.3662(12)
c (Å)	16.6969(5)	13.48050(10)	21.3305(18)
α (°)	98.7490(10)	90.00	90.00
β (°)	91.2890(10)	113.1140(10)	102.189(5)
γ (°)	102.3670(10)	90.00	90.00
V (Å³)	1614.89(8)	3450.52(7)	3304.6(5)
μ (mm⁻¹)	3.139	2.976	2.986
F(000)	728	1592	1528
Reflections Collected	14098	14591	18757
Unique reflections, R_{int}	5929, 0.0222	3162, 0.0247	6020; 0.0361
R1, wR2 [I>2σ(I)]	0.0290; 0.0664	0.0315, 0.0793	0.0359; 0.0569
R1, wR2 (all data)	0.0386; 0.0703	0.0397, 0.0840	0.0752; 0.0833
GooF	1.032	1.039	1.029

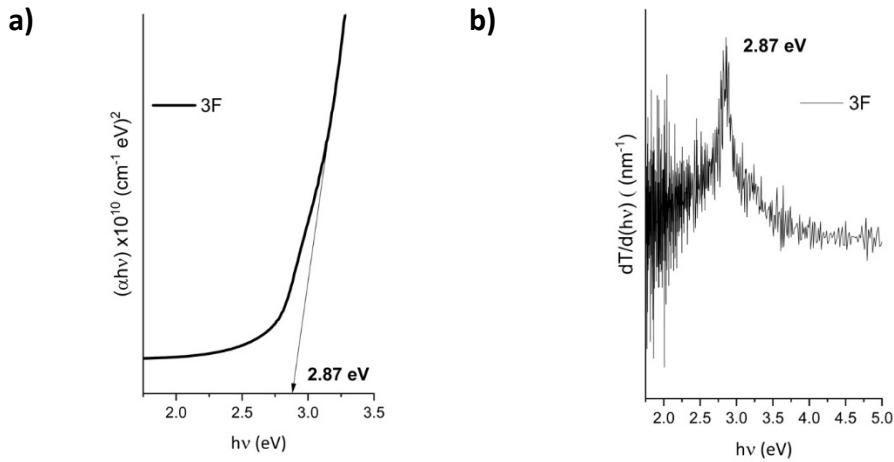
3. **Fig. S1.** Micrographs of annealed zinc thin films (**3Fa** and **4Fa**). **3Fa** SEM images (magn. 10000x and 60000x), AFM phase (1 x 1 μm) micrographs. **4Fa** SEM images (magn. 10000x and 60000x), and AFM phase (1 x 1 μm) micrographs.



4. Fig. S2. Micrographs of annealed cadmium thin films (**5Fa** and **6Fa**). **5Fa** SEM images (magn. 10000x and 60000x), AFM phase ($1 \times 1 \mu\text{m}$) micrographs. **6Fa** SEM images (magn. 10000x and 60000x), and AFM phase ($1 \times 1 \mu\text{m}$) micrographs.



5. **Fig. S3.** Optical band gap (E_g) estimation. Example of a) $(\alpha h\nu)^2$ versus photon energy ($h\nu$) plot for as-deposited $Zn_{1.41}S_{0.40}Se_{0.60}$ film (**3F**, as-deposited at 450°C) and b) the first derivative plot of transmittance spectra ($dT/d(h\nu)$).



a) The optical band gap (E_g) were estimated using Tauc's relationship:⁴

$$\alpha h\nu = B(h\nu - E_g)^{1/m} \quad (4)$$

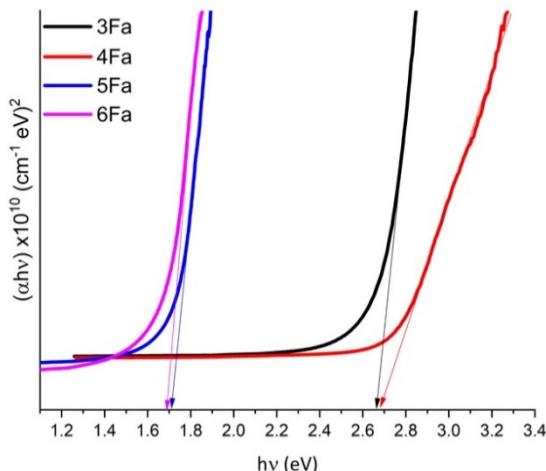
$$\alpha = -\frac{1}{t} \ln T \quad (5)$$

$$E_{\text{phonon}} = \frac{hC}{\lambda} \quad (6)$$

where α is the absorption coefficient, $h\nu$ is the incident photon energy, B is the energy-dependent constant, E_g is the optical band gap of the material, and m is the transition coefficient which can be 1/2, 3/2, 2, and 3, in this case $m = 2$ for direct allowed transitions and α was evaluated using the following relation (5) where t is the film thickness, T the transmittance. The optical energy gap, E_g of the investigated MSe thin films, were obtained from plot $(\alpha h\nu)^2$ versus the photon energy ($h\nu$) by extrapolating linear part to intersect ($h\nu$) axis at $(\alpha h\nu)^2 = 0$ (Fig. S4 for annealed films).

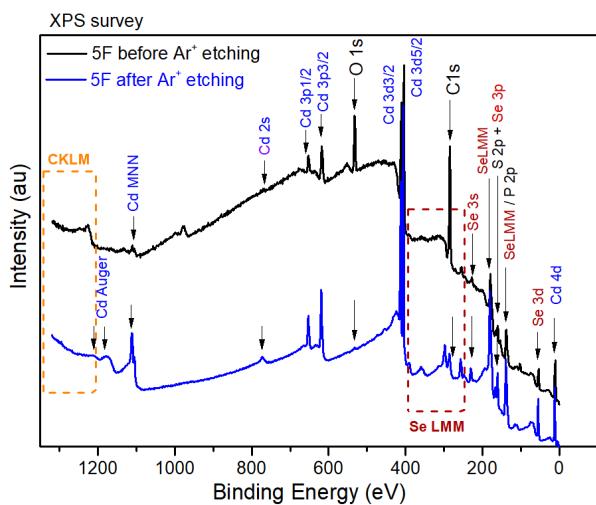
b) Similar values were obtained by means of the first derivative plots of transmittance spectra ($dT/d(h\nu)$).⁵

6. **Fig. S4.** Optical band gap (E_g) estimation. Plot of $(\alpha h\nu)^2$ versus photon energy ($h\nu$) for annealed zinc and cadmium films(**3Fa-6Fa**, annealed at 600°C).

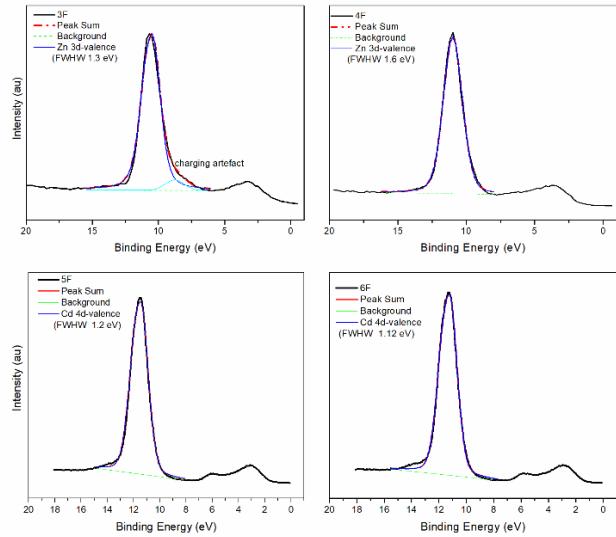


7. **Fig. S5** **a)** XPS survey spectra of **5F** before and after Ar⁺ etching process (as an example showing the disappearance of O-1s and C-1s features after etching process). Core-level HR-XPS spectra: **b)** Valence bands and corresponding Zn-3d (**3F** and **4F**) and Cd-4d (**5F** and **6F**), **c)** Zn 3s, Se LMM, P 2p region (**3F** and **4F**) and Se LMM, P 2p region (**5F** and **6F**), **d)** O 1s for **3F**-**6F**.

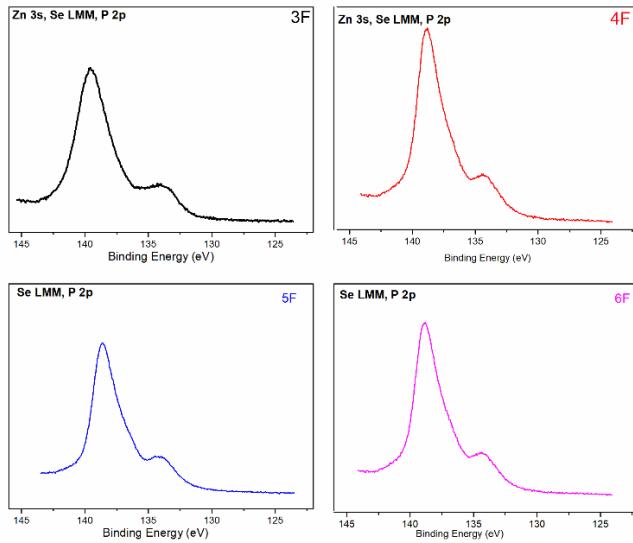
a)



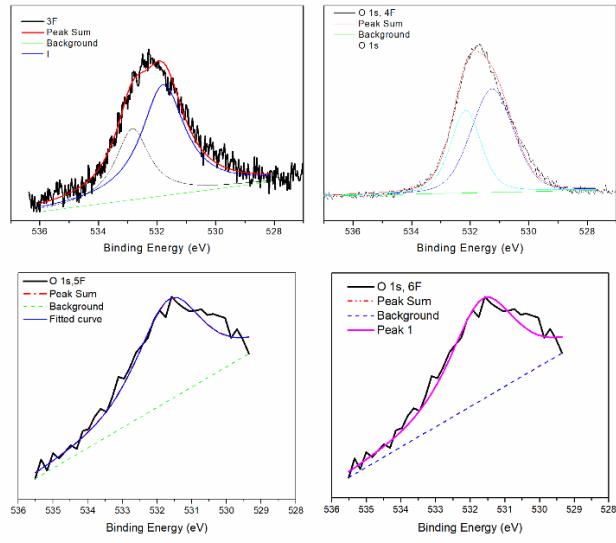
b)



c)



d)



Experimental details. XPS spectra were performed on stored **3F**-**6F** (Thermo K-alpha spectrometer, Al K α X-ray source, 1486.68 eV). The samples were introduced into an ultra-high vacuum (UHV) chamber (1×10^{-7} - 1×10^{-8} Pa) and measured at room temperature. For every sample, survey spectra and individual core level spectra were obtained under the same conditions before and after Ar⁺ etching (initial and final spectra). Depth profile was acquired until the intensity of core level peaks reached to constant value. The spot size in the beam was 300 μm and the pass energy was set to 150 eV for the survey spectra (energy step 1.0 eV), 25 eV for recording C1s and O1s, and 50 eV for recording the individual core level spectra. 10 scans were performed for C 1s, Cd 4d, Cd 3d, O1s, P 2p, S 2p, Se 3p, Se 3d and Zn 2p core level with an energy step size of 0.030 eV except for O1s (0.020 eV), S 2p (0.022 eV), Se 3p (0.025 eV), Se 3d (0.021 eV) and Zn 2p (0.06 eV). The relative atomic concentrations were

determined from the primary core level XPS peak (Cd-3d, O-1s, S-2p, Se-3d and Zn-2p) and the sensitive factors provided by the XPS apparatus (SDPv4.1 software[®]). The high-resolution regions of interest were fitted using Tougaard or linear background with a symmetric Gauss-Lorentz sum function.

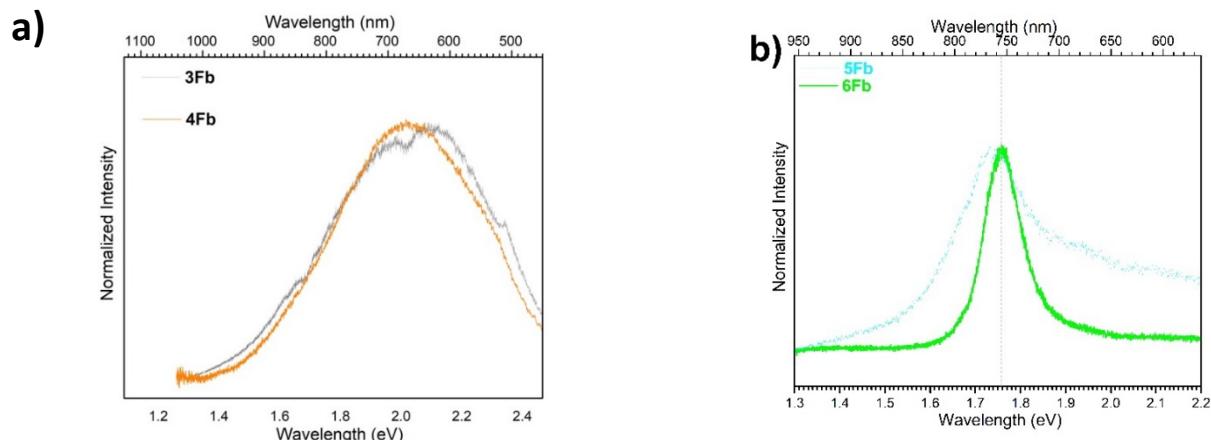
8. Table S2. Band gaps (E_g) of our films* and related MSe and MSSe thin films obtained from different precursors and/or technique.

Material	Precursor	Preparation method (solvent)	T _{prep} (°C)	Eg (eV)	Ref
ZnSSe	[Zn{Pr ₂ P(Se)NC(S)NC ₅ H _{10-K²-Se,S}]₂] (3)}	AACVD (Toluene)	375	2.93	*
ZnSSe	[Zn{Pr ₂ P(Se)NC(S)NC ₅ H _{10-K²-Se,S}]₂] (3)}		450	2.87	*
ZnSSe	[Zn{Pr ₂ P(Se)NC(S)NC ₅ H _{10-K²-Se,S}]₂] (3)}		annealed (600)	2.67	*
ZnSe	[Zn{Pr ₂ P(Se)NC(O)NC ₅ H _{10-K²-Se,O}]₂] (4)}		375	2.74	*
ZnSe	[Zn{Pr ₂ P(Se)NC(O)NC ₅ H _{10-K²-Se,O}]₂] (4)}		450	2.71	*
ZnSe	[Zn{Pr ₂ P(Se)NC(O)NC ₅ H _{10-K²-Se,O}]₂] (4)}		annealed (600)	2.68	*
ZnSe	[Zn(Se ₂ CNEt ₂) ₂]	AACVD (THF)	350	2.25	6
Zn _x Se _{1-x} Se _{rich}	[Zn(Se ₂ CNEt ₂) ₂]:[Zn(Se ₂ CNEt ₂) ₂] 1:0.75		350	2.55	6
1:1 (S:Se)	[Zn(Se ₂ CNEt ₂) ₂]: [Zn(Se ₂ CNEt ₂) ₂] 1:1		350	2.66	6
ZnSe	Na ₂ SeSO ₃ + Zn ²⁺	CBD	25,	3.04	7
			45	3.02	
			60	2.89	
			80	2.82	
ZnSe	[Zn(Pr ₂ P(Se)NP(Se)/Pr ₂) ₂]	LP-MOCVD	425-450	2.63	8
ZnSe	Zn(CH ₃ COO) ₂ ·2H ₂ O and SeO ₂	Electrodeposition by three-electrode set-up (water)	27	2.7	9
ZnSe	ZnSO ₄ and Na ₂ (SeSO ₃)	CBD (water)	80	2.65	10
ZnSe	ZnSO ₄ ·7H ₂ O, SeO ₂ Using different complexing agents: Ammonia Citric acid EDTA Ethylenediamine Hydrazine hydrate Polyvinyl alcohol Triethanolamine	Electrochemical deposition	50		11
ZnS	ZnS and ZnSe powder				12
ZnS _{0.73} Se _{0.27}				3	
ZnS _{0.68} Se _{0.32}				2.82	
ZnS _{0.36} Se _{0.64}				2.77	
ZnSe				2.68	
ZnSe	ZnSO ₄ , SeC(NH ₂) ₂ , NH4OH (25%), Varying (hydrazine hydrate) : (Na ₃ -citrate) Sol. A (0:10) Sol. B (2:8) Sol. C (3:7) Sol. D (5:5) Sol. E (7:3) Sol. F (8:2)	CBD	80		13
ZnSe				2.65	
ZnSe				2.69	
ZnSe				2.72	
ZnSe				2.95	
ZnSe				3.48	
ZnSe				3.55	
ZnSe	ZnSe powder As-deposited Annealed at 350 and 400	Pulsed laser deposition (2x10 ⁻²⁵ Torr, Nd:YAG(λ:355 nm))		2.65	14
ZnSe				annealed (350)	
ZnSe				annealed (400)	
ZnSe	ZnSe particles (99.99%)	Electron beam evaporation technique (2.0×10 ⁻³ Pa) and annealed at:	as-deposited	2.75	15
ZnSe			300	2.58	
ZnSe			400	2.52	
ZnSe			500	2.43	
ZnSe			600	2.43	
ZnSe	100 mM ZnSO ₄ and 1 mM SeO ₂ in H ₂ SO ₄ and NaOH (pH=2)	Electrodeposition on Pt electrodes	RT	2.73	16
ZnSe	ZnSO ₄ , Se, Na ₂ SO ₃ , Na ₃ -citrate, triethanolamine (TEA), hydrazine hydrate, and NaOH (pH),	Solution growth technique (SGT).	80	2.71	17
CdSSe	[Cd{Pr ₂ P(Se)NC(S)NC ₅ H _{10-K²-Se,S}]₂] (5)}		375	1.80	*
CdSSe	[Cd{Pr ₂ P(Se)NC(S)NC ₅ H _{10-K²-Se,S}]₂] (5)}		450	1.77	*

CdSSe	[Cd{ $\text{Pr}_2\text{P}(\text{Se})\text{NC}(\text{S})\text{NC}_5\text{H}_{10-\kappa^2}\text{-Se},\text{S}_2$ }] (5)	AACVD (Toluene)	annealed (600)	1.71	*
CdSe	[Cd{ $\text{Pr}_2\text{P}(\text{Se})\text{NC}(\text{O})\text{NC}_5\text{H}_{10-\kappa^2}\text{-Se},\text{O}_2$ }] (6)		375	1.76	*
CdSe	[Cd{ $\text{Pr}_2\text{P}(\text{Se})\text{NC}(\text{O})\text{NC}_5\text{H}_{10-\kappa^2}\text{-Se},\text{O}_2$ }] (6)		450	1.74	*
CdSe	[Cd{ $\text{Pr}_2\text{P}(\text{Se})\text{NC}(\text{O})\text{NC}_5\text{H}_{10-\kappa^2}\text{-Se},\text{O}_2$ }] (6)		annealed (600)	1.69	*
CdSe	[Cd($\text{Pr}_2\text{P}(\text{Se})\text{NP}(\text{Se})\text{Pr}_2$) ₂]	LP-MOCVD	475-500	1.71	8
CdSe	[MeCd($\text{Pr}_2\text{P}(\text{Se})\text{NP}(\text{Se})\text{Pr}_2$) ₂]	LP-MOCVD	450	1.73	18
CdSe	[Cd(Se_2CNET_2) ₂] ₂	AACVD (THF)	300	1.75	19
CdS_{0.2}Se_{0.8} CdS_{0.4}Se_{0.6}	[Cd(Se_2CNET_2) ₂] ₂ :[Cd(S_2CNET_2) ₂] ₂ (1:1 & 2:1)	AACVD (THF)	300	1.9 2.0	19
n-CdSeS	CdCl ₂ , KI, elemental Se and S)	galvanostatic method	130	2.26 - 2.48	²⁰
CdSe	CdSe NPs	CBD	RT	2.41	²¹
			60	2.36	
			70	2.25	
			80	2.38	
CdS	CdS _{1-x} Se _x /TO thin films	CBD during 2 h	90	2.37	²²
CdS _{0.75} Se _{0.25}	0.1 M CdCl ₂ + 0.33 M CS(NH ₂) ₂ + 0.1 M Na ₂ SeSO ₃ solutions (different proportions)			2.18	
CdS _{0.5} Se _{0.5}				2.02	
CdS _{0.25} Se _{0.75}				1.92	
CdSe				1.86	
CdS CdS_xSe_{1-x} CdSe	CdSO ₄ ·8H ₂ O, HClO ₄ , NH ₄ OH, CH ₃ COONa·3H ₂ O, CH ₃ COOH, Na ₂ S	electrochemical atomic layer epitaxy (ECALE)		2.42-1.64	²³
CdS_{0.5}Se_{0.5}	Cadmium sulfide, cadmium selenide and cadmium chloride sintering process.	screen-printing method	120	2.1	²⁴
CdS_{0.5}Se_{0.5}	cadmium chloride, thiourea and sodium seleno-sulphate and 8-hydroxyquinoline	CBD	70	2.2	²⁵
CdS_{0.55}Se_{0.45}	CdS _{1-x} Se _x nanocrystals in a borosilicate glass matrix from commercially available samples	diffusion-limited growth (solid-state precipitation)		2.45	²⁶
CdS_{0.75}Se_{0.25}	CdCl ₂ (0.033 M), Cd(NH ₂) ₂ (0.033 M), Na ₂ SeSO ₃ (0.1 M). Deposition time (min):	Chemical solution deposition	75		²⁷
			60	2.25	
			120	2.28	
			180	2.27	
CdS_{0.8}Se_{0.2}	CdS _{1-x} Se _x thin film: CdSO ₄ (0.1 M) and thiourea (0.2 M)	CBD (in air)	80±75	2.16	²⁸
CdS _{0.6} Se _{0.4}	CdSO ₄ (20mL) + thiourea + Na ₂ (S(Se)O ₃)		"	2.03	
CdS _{0.4} Se _{0.6}	" " "		"	1.97	
CdS _{0.2} Se _{0.8}	CdSO ₄ + Na ₂ (S(Se)O ₃)		"	1.8	
CdSe			50±5 °C	1.73	
2D CdS _x Se _{1-x} alloy	CdCl ₂ (s)+ S(s) + Se(s)	PVD	800	1.8-2.3 PL	²⁹
CdS	CdS and CdSe (99.999%)	Thermal co-evaporation of source materials (2 × 10 ⁻⁶ mbar)	RT	2.43	³⁰
CdS _{0.8} Se _{0.2}				2.13	
CdS _{0.6} Se _{0.4}				1.99	
CdS _{0.4} Se _{0.6}				1.83	
CdS _{0.2} Se _{0.8}				1.79	
CdSe				1.65	

*This work

9. Fig. S6. PL spectra ($\lambda_{\text{ex}} = 488 \text{ nm}$) of as-deposited films at 375°C: a) 3Fb and 4Fb, and b) 5Fb and 6Fb.



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